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				Application Number	Not assigned yet			
INFORMATION DISCLOSURE STATEMENT BY APPLICANT (use as many sheets as necessary)				Filing Date	On even date herewith			
				First Named Inventor	J. YUGAMi, et al.			
				Art Unit	Not assigned yet			
				Examiner Name	Not assigned yet			
Sheet	1	of	1	Attorney Docket Number	520.40885VX1			

U.S. PATENT DOCUMENTS					
Examiner Initials'	Cite No.1	Document Number Number-Kind Code ² (if known)	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
SRG		6,495,890 B1	12-2002	Ono	
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Examiner	Cite	Foreign Patent Document	Publication Date	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear	₹°
Initials'	No.	Country Code ³ -Number ⁴ -Kind Code ⁶ (if known)	MM-DD-YYYY			
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OTHER PRIOR ART—NON PATENT LITERATURE DOCUMENTS					
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500		1998 International Electron Electron Device Meeting Technical Digest, (Pgs. 1038-1040), A 1.1 nm Oxide Equivalent Gate Insulator Formed Using TiO2 on Nitrided Silicon.			
506		IEEE Transactions on Electron Devices, Vol. 46, No. 7, July 1999, (Pages 1537-1544), The Impact of High-k Gate Dielectrics and Metal Gate Electrodes on Sub-100 nm MOSFET's			
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Examiner Signature	AND By	Date Considered	7.20.04

^{*}EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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